

Training Procedure

- 1) Training request can be filed by sending a mail to **SO** with **CC** to your guide and the assistant lab manager_ with brief details of your project and purpose of use of tool.
- 2) Some basic knowledge of FURNACES and thermal oxidation procedure is necessary. You may refer to the slides of the course EE669, available on the INUP server/computer.
- 3) In the first training session, system overview will be given by the system owner or AU.
- 4) In the second session, we will give some hardware knowledge, i.e. about temperature controllers, gas handling and loading of wafers.
- 5) In the third session 2 Demo runs will be given by SO or AU.
- 6) After training, 1 Hands On in presence of any authorized user. In Hands on whole process should be done by applicant.
- 7) After Demo run Authorization test will be held in presence of System Owner.

Violation policy:

1. User should not violate any of the steps mentioned in SOP.
2. Do not leave the system while the process is running.
3. Book your process slots well in advance using the online slot booking system.
4. User should use the slot that he/she has booked.
5. For a fair distribution of slots, don't over-book them.
6. Don't forget to make a log book entry for process.
7. Only RCA cleaned VLSI grade Silicon wafers are allowed in the furnace. Don't try new materials and do not make any hardware changes in the system without System owner's permission.
8. Do NOT use the furnace during night time (6pm-9am).

If it is found that user is not following the above rules and regulations, then his/her authorization may be cancelled or any other punishable measure can be taken after discussion with faculty in-charge of this tool.